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w Drawing chg.
E. Millis
3-7-03

PATENT
5018/ISM/MCVD/BG
7828.7056

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of)	Examiner: not assigned
Tepman, et al.)	
Serial No.: 10/074,854)	Art Unit: 2812
Filing Date: February 11, 2002)	

For: VARIABLE FLOW DEPOSITION APPARATUS AND METHOD IN SEMICONDUCTOR
SUBSTRATE PROCESSING

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents
Washington, D.C. 20231

Dear Sirs:

Prior to issuing a first action in the above-referenced application, please enter and consider the following amendments:

IN THE DRAWINGS:

Please amend Figure 2 as shown in red in the attached drawings.

IN THE SPECIFICATION:

Please replace paragraphs 0014, 0016, 0019, 0020, and 0022-26 with the following rewritten paragraphs:

[0014]

Fig. 1 is a cross sectional view of a single substrate ALD chamber in accordance with aspects of the present inventions.